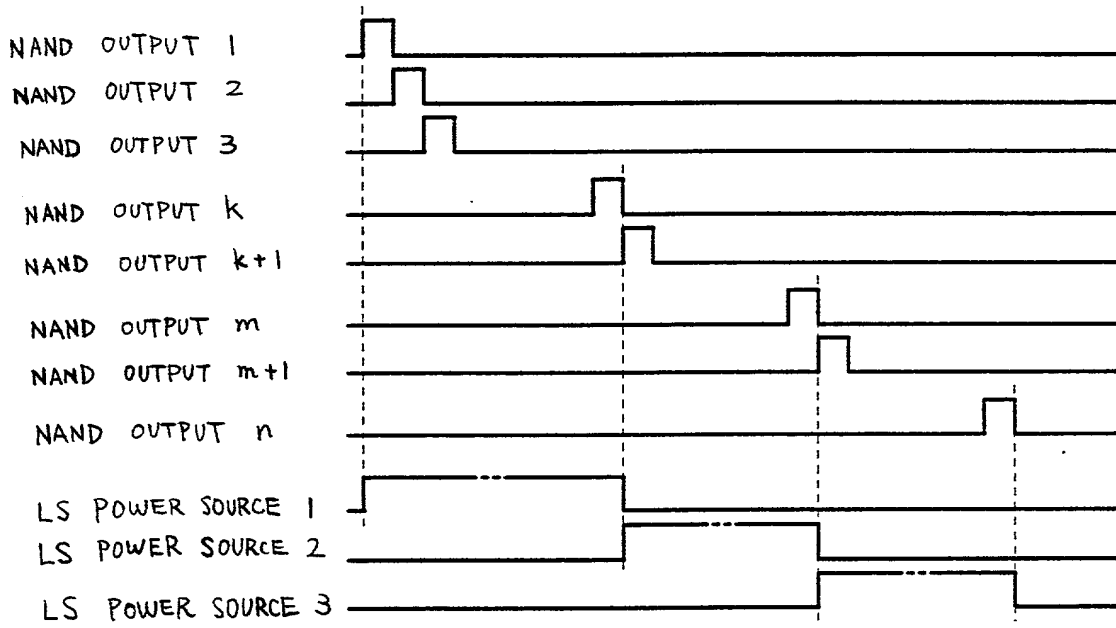


Fig. 2

Fig. 4



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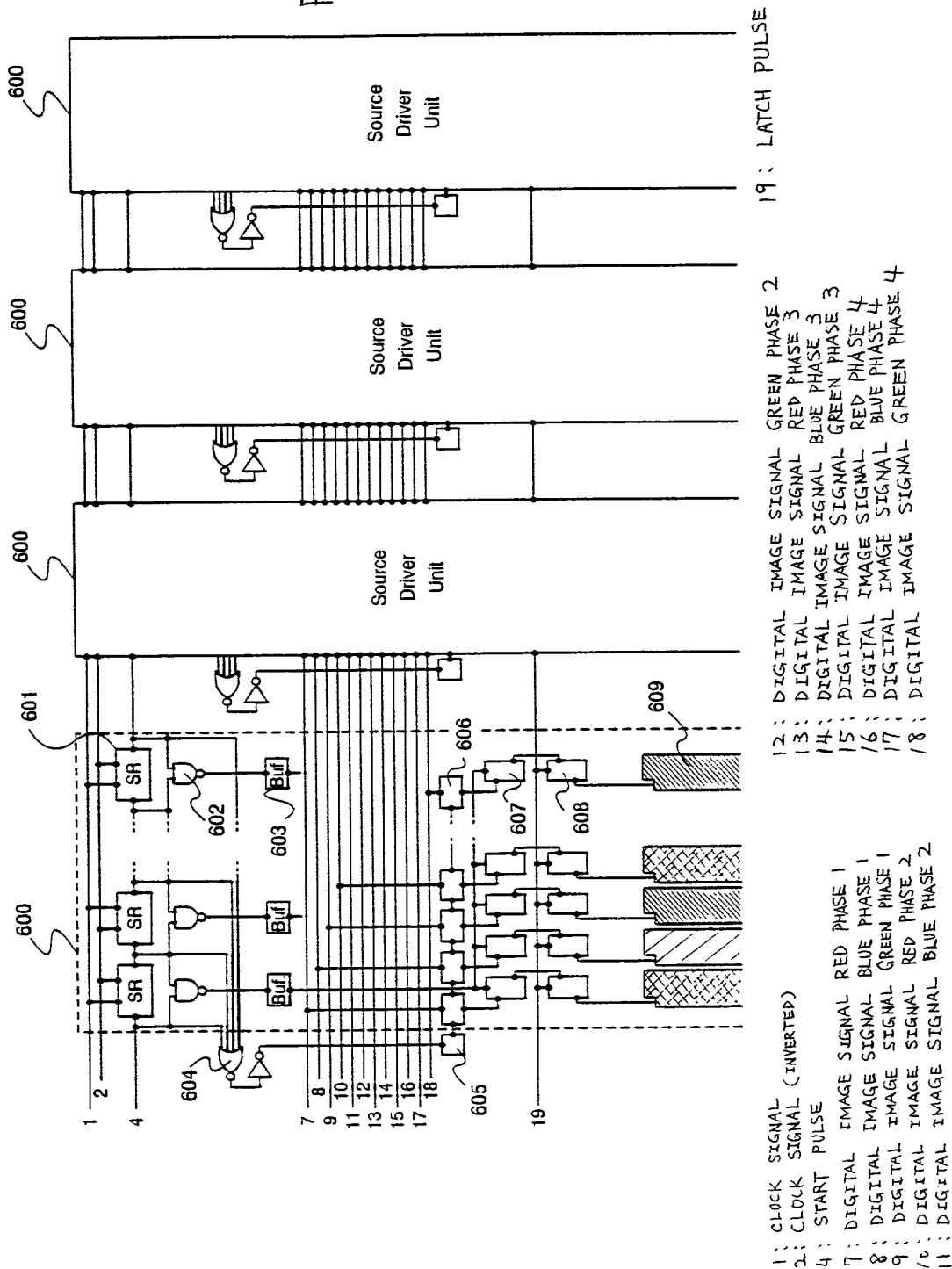
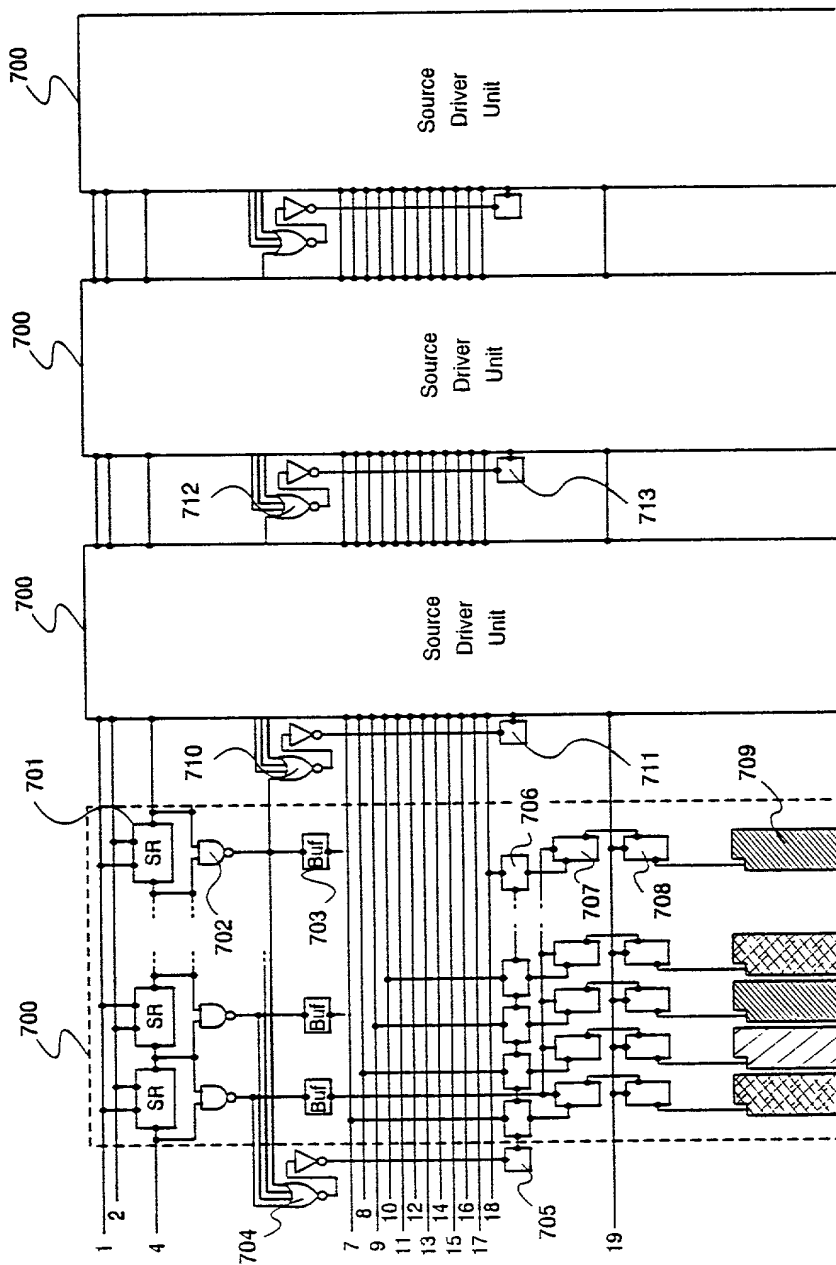


Fig. 6



- 1: CLOCK SIGNAL
- 2: CLOCK SIGNAL (INVERTED)
- 4: START PULSE
- 8: DIGITAL IMAGE SIGNAL BLUE PHASE 1
- 9: DIGITAL IMAGE SIGNAL GREEN PHASE 1
- 10: DIGITAL IMAGE SIGNAL RED PHASE 1
- 11: DIGITAL IMAGE SIGNAL BLUE PHASE 2
- 12: DIGITAL IMAGE SIGNAL GREEN PHASE 2
- 13: DIGITAL IMAGE SIGNAL RED PHASE 3
- 14: DIGITAL IMAGE SIGNAL BLUE PHASE 3
- 15: DIGITAL IMAGE SIGNAL GREEN PHASE 4
- 16: DIGITAL IMAGE SIGNAL RED PHASE 4
- 17: DIGITAL IMAGE SIGNAL BLUE PHASE 4
- 18: DIGITAL IMAGE SIGNAL GREEN PHASE 4
- 19: LATCH PULSE

Fig. 7

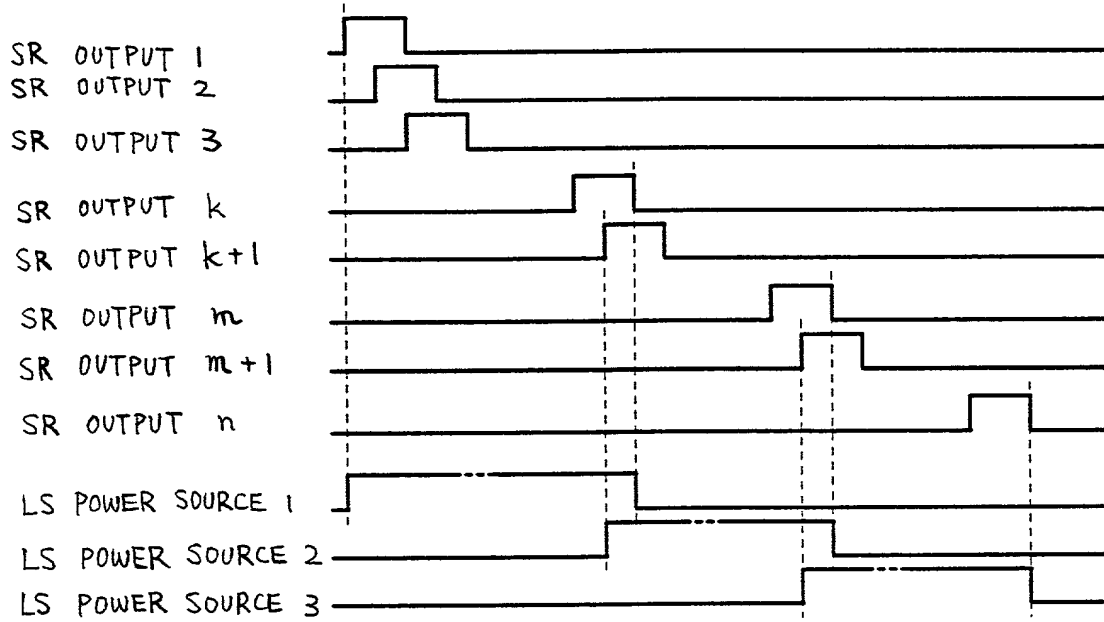


Fig. 8(A)

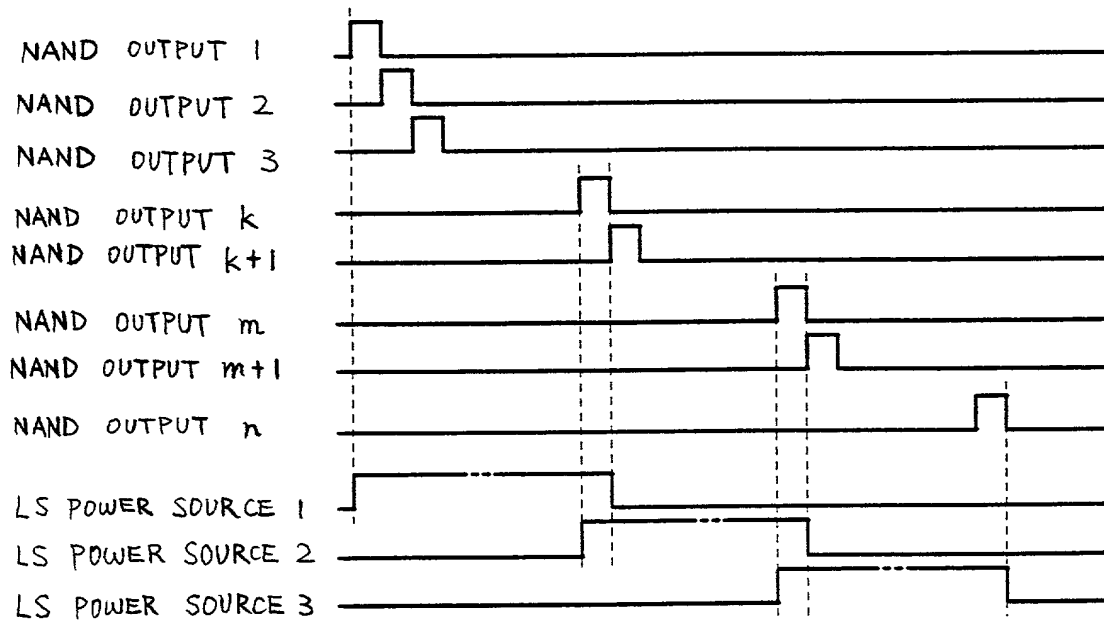


Fig. 8(B)

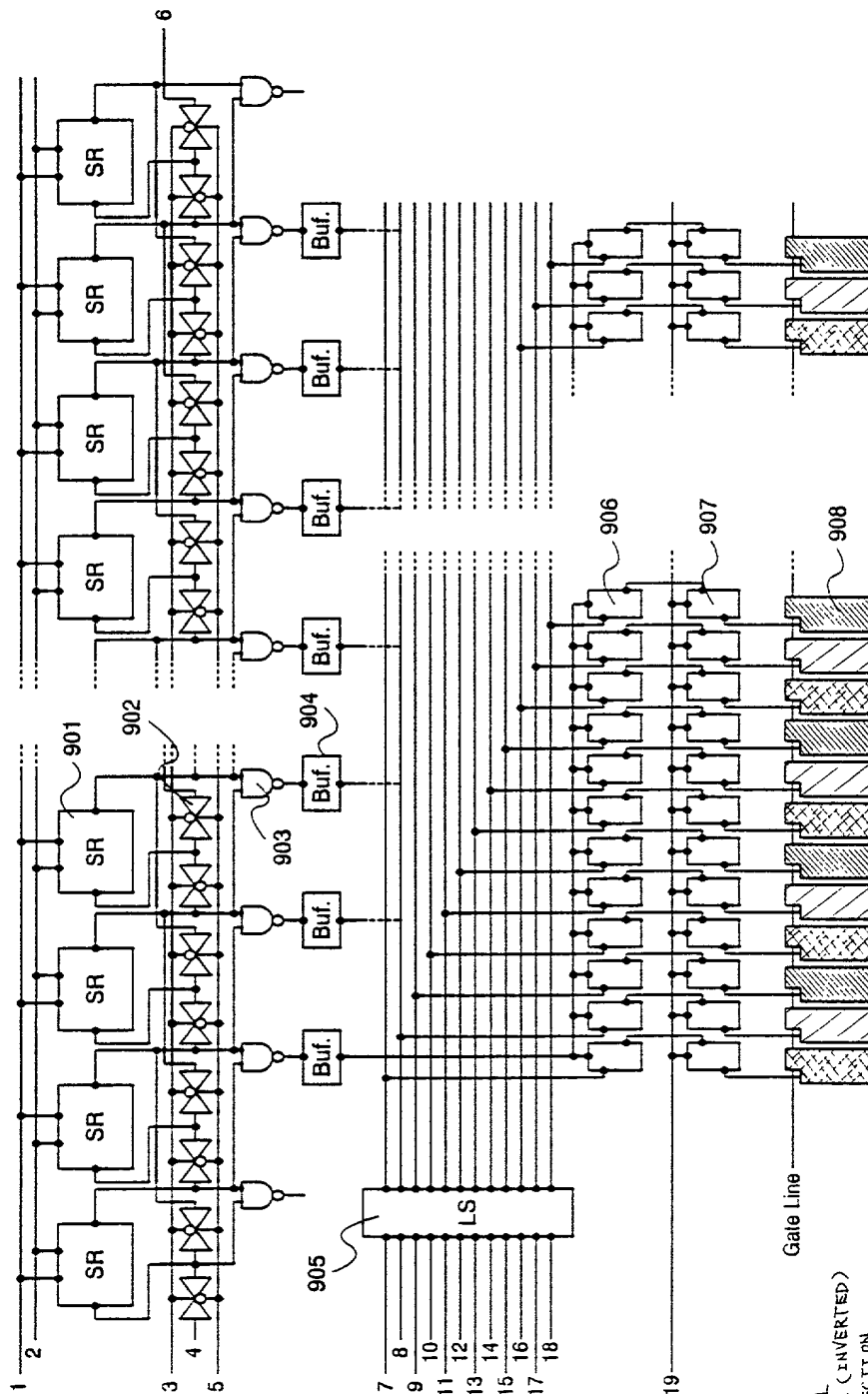


Fig. 9

- 1: CLOCK SIGNAL (INVERTED)
- 2: CLOCK SIGNAL (INVERTED)
- 3: SCANNING DIRECTION CONTROL SIGNAL
- 4: START PULSE (L→R)
- 5: SCANNING DIRECTION CONTROL SIGNAL (INVERTED)
- 6: START PULSE (R→L)
- 7: DIGITAL IMAGE SIGNAL RED PHASE 1
- 8: DIGITAL IMAGE SIGNAL BLUE PHASE 1
- 9: DIGITAL IMAGE SIGNAL GREEN PHASE 1
- 10: DIGITAL IMAGE SIGNAL RED PHASE 2
- 11: DIGITAL IMAGE SIGNAL BLUE PHASE 2
- 12: DIGITAL IMAGE SIGNAL GREEN PHASE 2
- 13: DIGITAL IMAGE SIGNAL RED PHASE 3
- 14: DIGITAL IMAGE SIGNAL BLUE PHASE 3
- 15: DIGITAL IMAGE SIGNAL GREEN PHASE 3
- 16: DIGITAL IMAGE SIGNAL RED PHASE 4
- 17: DIGITAL IMAGE SIGNAL BLUE PHASE 4
- 18: DIGITAL IMAGE SIGNAL GREEN PHASE 4
- 19: LATCH PULSE

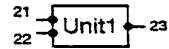
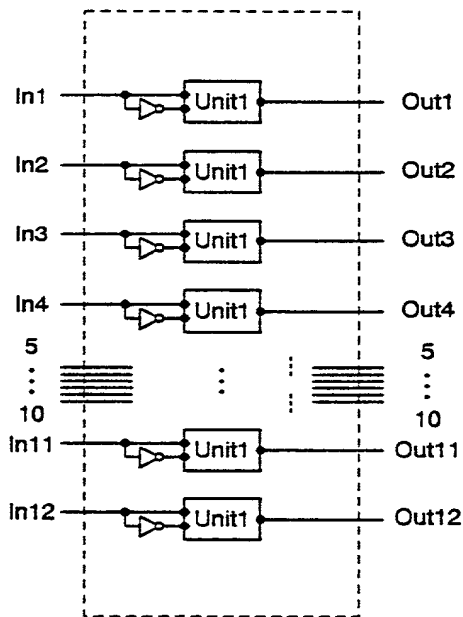


Fig. 10(A)

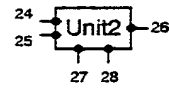
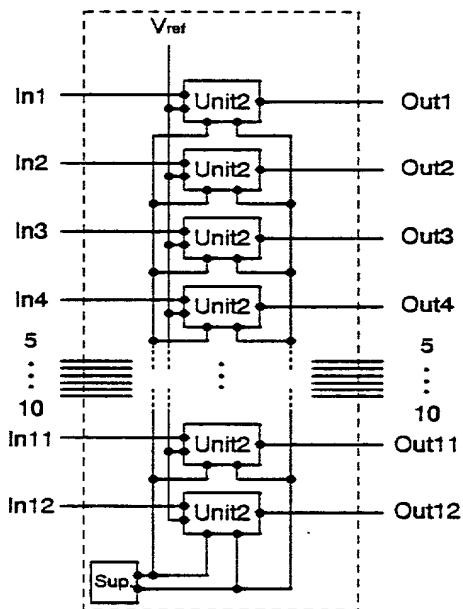
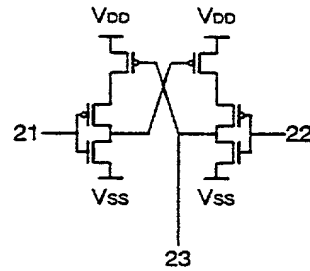
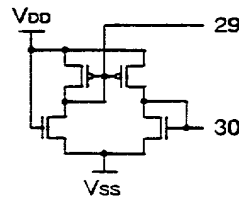
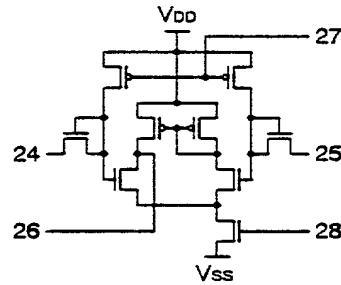


Fig. 10(B)



FORMATION OF SEMICONDUCTOR ISLAND AND FIRST AND SECOND CONDUCTIVE FILMS FOR GATE ELECTRODE

Fig. 1(A)

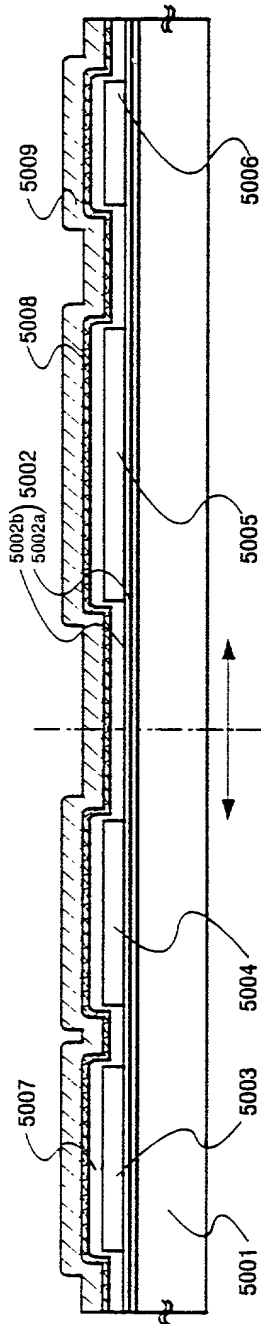


Fig. 1(B)
FIRST ETCHING PROCESS AND
FIRST DOPING PROCESS

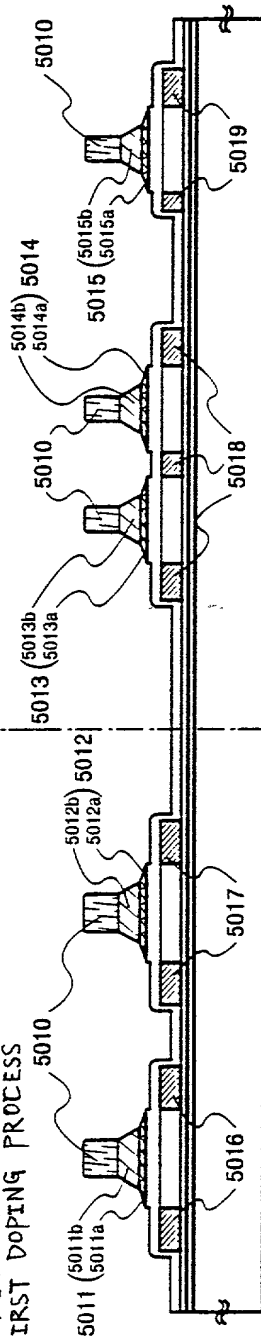


Fig. 1(C)
SECOND ETCHING PROCESS

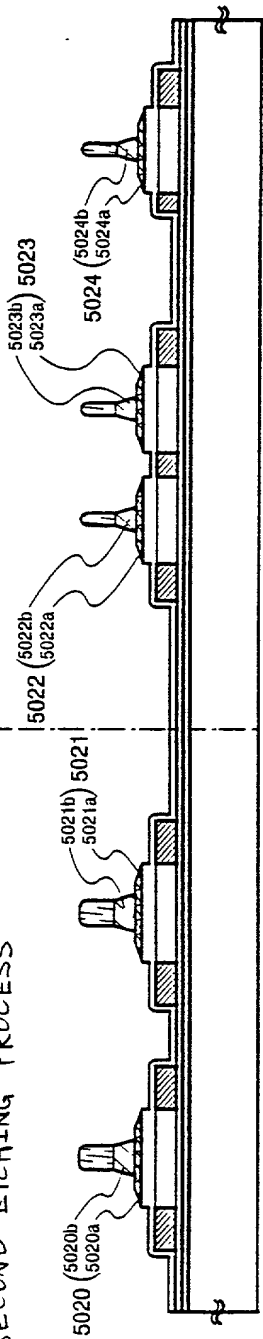


Fig.12(A) SECOND DOPING PROCESS

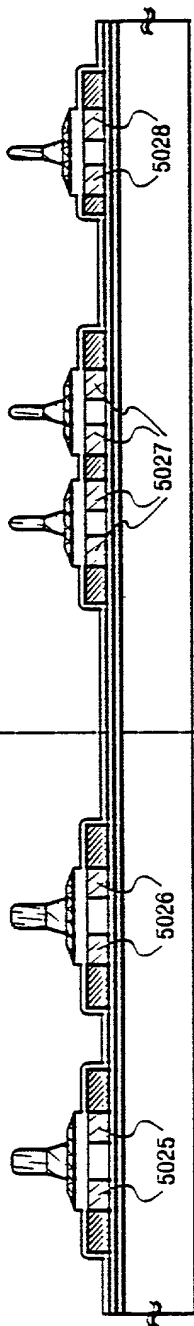


Fig.12(B)

THIRD ETCHING
PROCESS

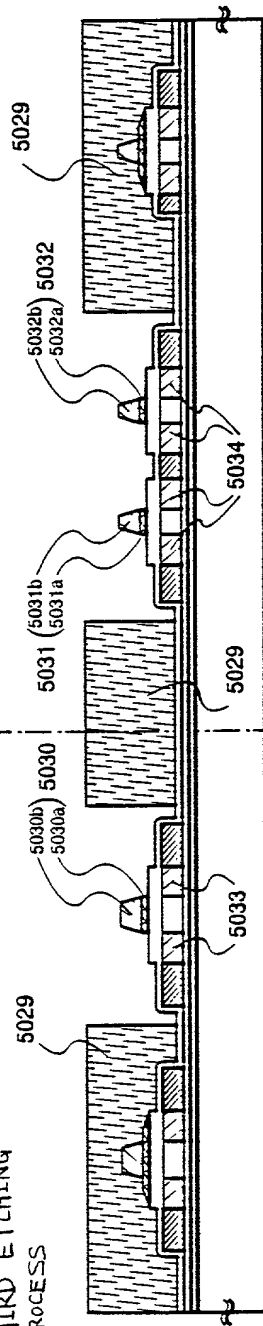
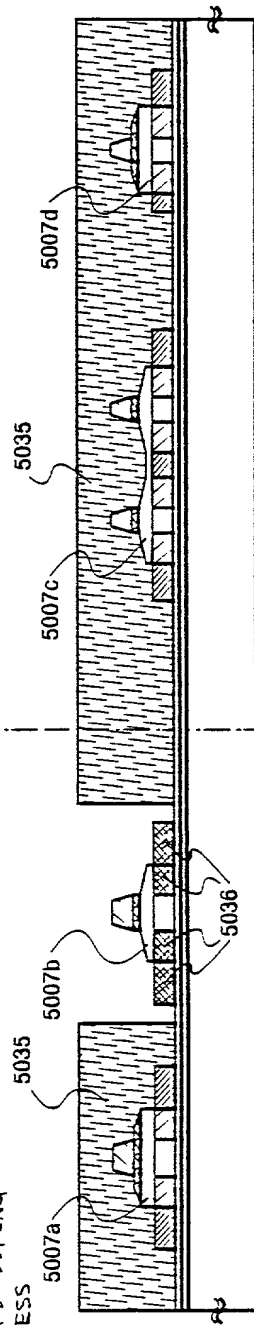


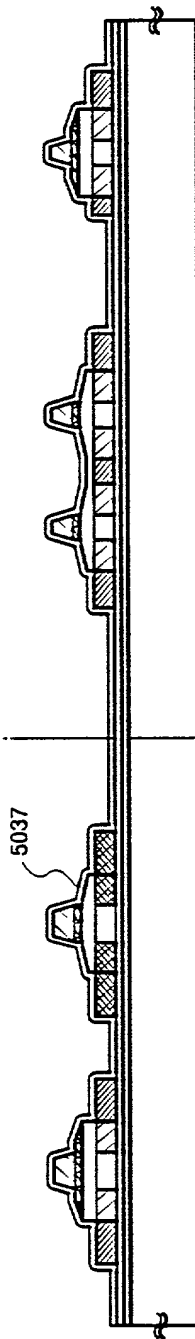
Fig.12(C)

THIRD DOPING
PROCESS



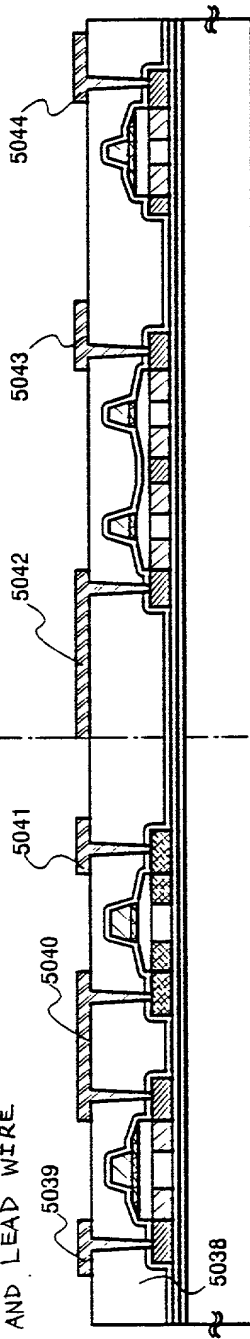
FORMATION OF FIRST INTER-LAYER
INSULATING FILM / ACTIVATION PROCESS

Fig.13(A)



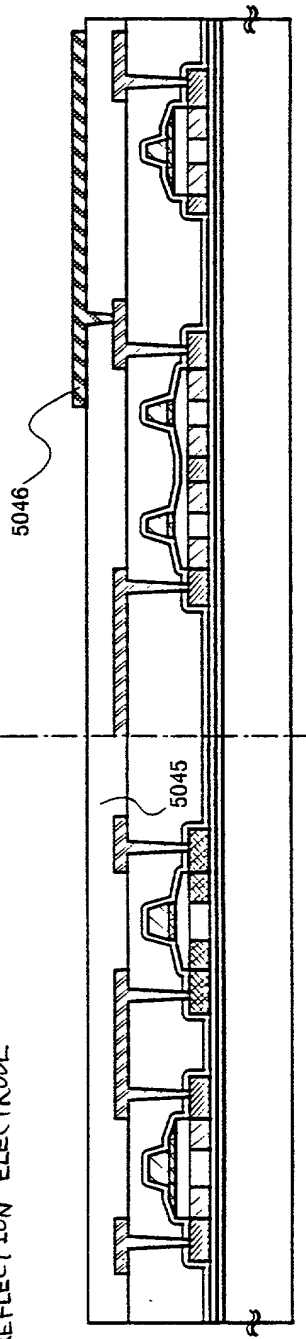
FORMATION OF SECOND INTER-LAYER INSULATING
FILM AND LEAD WIRE

Fig.13(B)



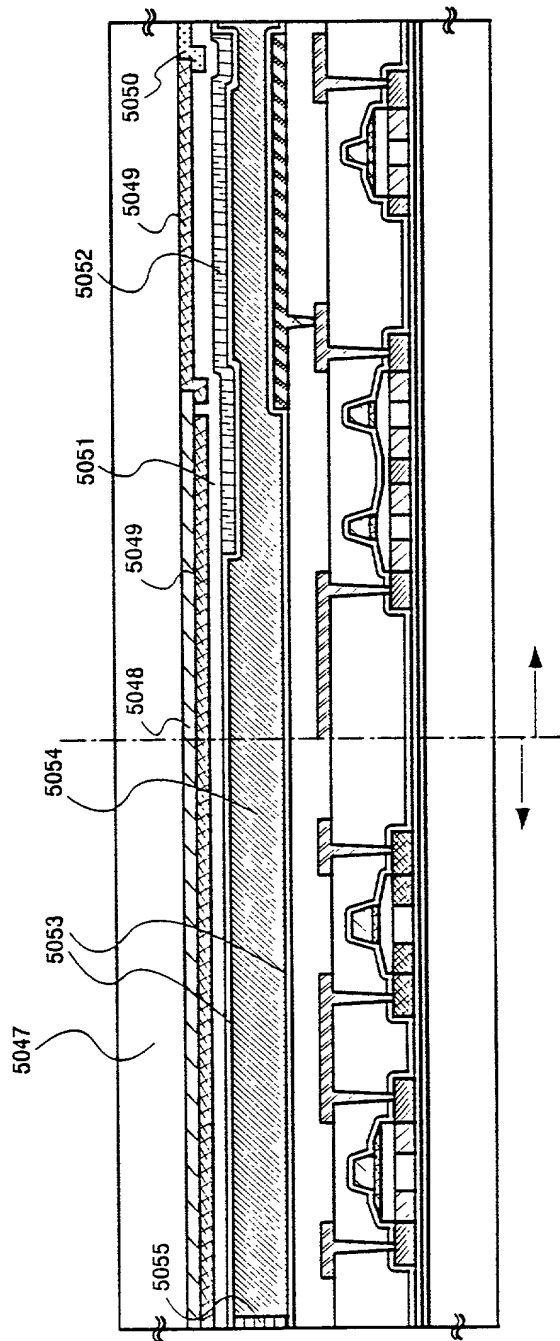
FORMATION OF THIRD INTER-LAYER INSULATING FILM
AND REFLECTION ELECTRODE

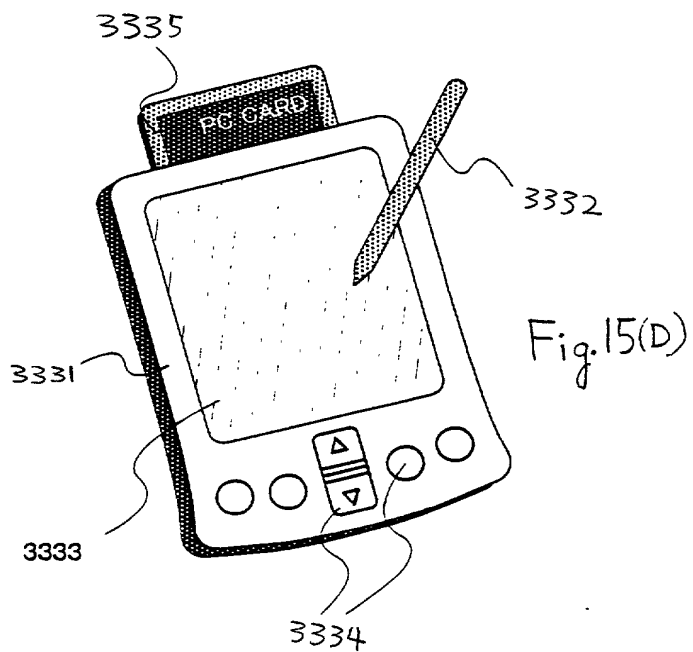
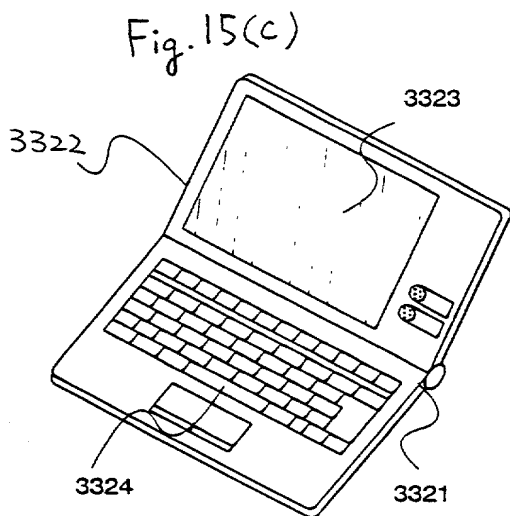
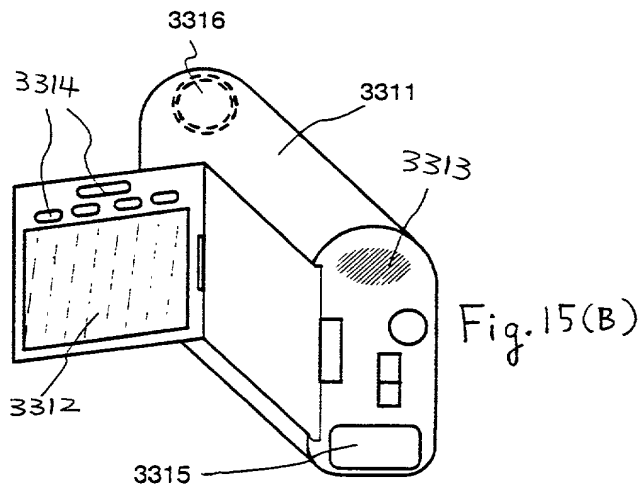
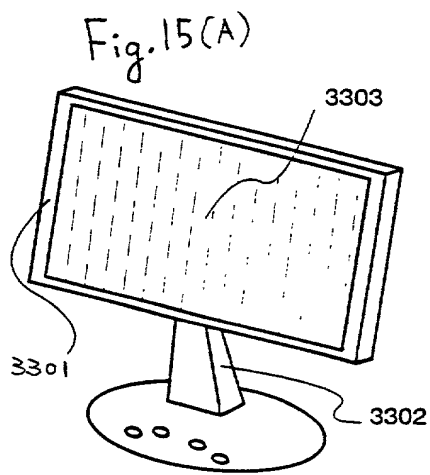
Fig.13(C)

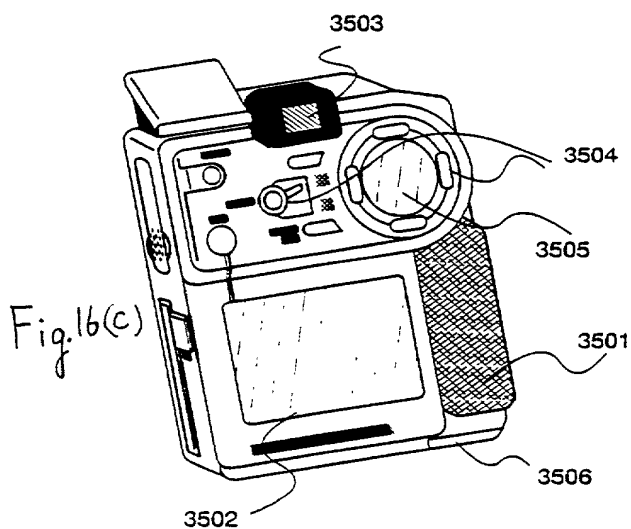
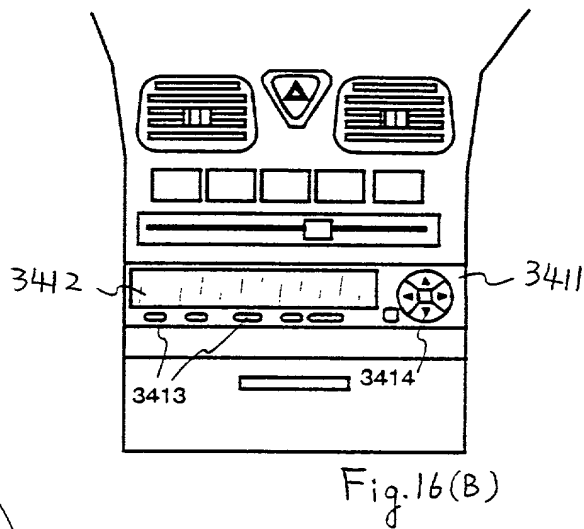
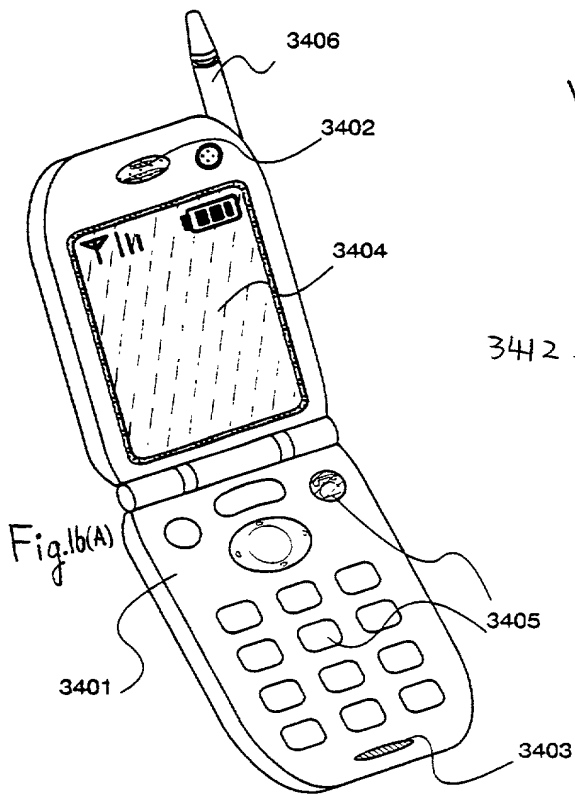


FORMATION OF OPPOSING SUBSTRATE/ INJECTION OF LIQUID CRYSTAL MATERIAL

Fig.14







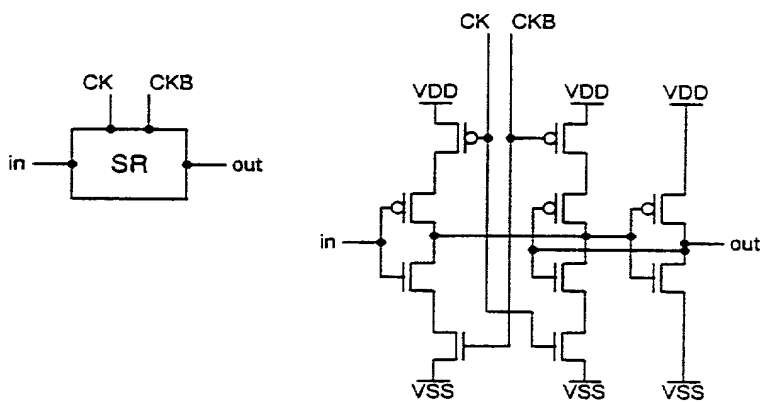


Fig. 17(A)

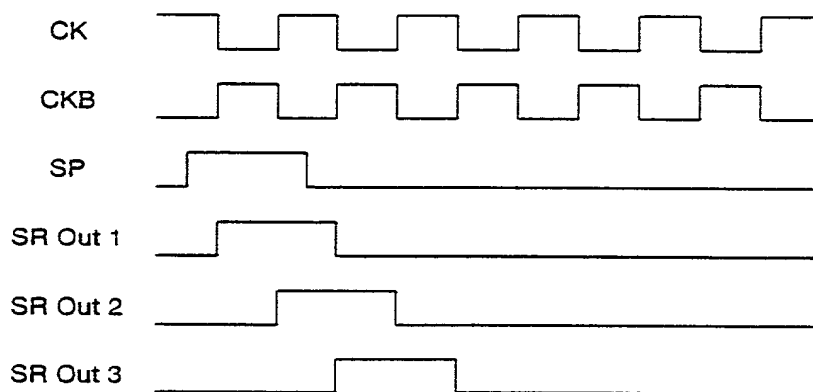


Fig. 17(B)